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(WO/2000/030747) MODIFIED PHOTOCATALYST SOL

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Applicants: ASAHI KASEI KABUSHIKI KAISHA [JP/JP]; 2-6, Dojimahama 1-chome, Kita-ku, Osaka-shi, Osaka 530-8205 (JP) (*All Except US*).
NAKABAYASHI, Akira [JP/JP]; Asahikasei-Kamiooka-shataku 1-302, 3-1-1, Ookubo, Konan-ku, Yokohama-shi, Kanagawa 233-0007 (JP) (*US Only*).

Inventor: NAKABAYASHI, Akira; Asahikasei-Kamiooka-shataku 1-302, 3-1-1, Ookubo, Konan-ku, Yokohama-shi, Kanagawa 233-0007 (JP).

Agent: YOSHIOKA, Masashi; 3rd Floor, Akasaka, Habitation Building, 3-5, Akasaka 1-chome, Minato-ku, Tokyo 107-0052 (JP).

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Title: MODIFIED PHOTOCATALYST SOL

Abstract: A modified photocatalyst sol comprising a liquid medium and modified photocatalyst particles dispersed therein, wherein the modified photocatalyst particles are ones obtained by modifying photocatalyst particles with at least one modifier compound selected among compounds each having at least one kind of structural units selected among monooxydiorganosilane units, dioxyorganosilane units, and difluoromethylene units and have a specific average particle diameter; and a modified photocatalyst composition comprising the modified photocatalyst sol and a functional substance. A film formed with the modified photocatalyst sol or modified photocatalyst composition, a functional composite comprising a substrate coated therewith, and a molded object are also provided.

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